LISTING OF CLAIMS

The listing of claims provided below replaces all prior versions, and listings, of claims in the application.

1. (Currently Amended) An electrostatic chuck, comprising:

a metal base plate;

a ~~disc-shaped~~ ceramic ~~layer~~ disc having a predetermined thickness adhesively bonded to said metal base plate;

a ~~planner~~ planar electrode positioned in the middle of said ceramic disc ~~layer in the middle thereof in its~~ relative to a thickness direction of said ceramic disc; and

a cooling gas channel ~~is~~ formed on a top surface of said ceramic disc ~~layer~~ over said electrode and within an outer peripheral edge of said electrode.

2. (Currently Amended) ~~The~~ An electrostatic chuck according to claim 1, wherein said ~~planner~~ planar electrode extends beyond said cooling gas channel.

3. (Currently Amended) An electrostatic chuck according to claim 1, wherein said cooling gas channel comprises a ring shape along an outer peripheral edge of said ceramic disc ~~layer~~, said chuck further comprising gas feed orifices located in a plurality of positions at a bottom portion of said gas cooling channel and gas feed orifices located in a plurality of positions on a circumference on a surface of said ceramic disc ~~layer~~ in the center side of the chuck.

4. (Currently Amended) An electrostatic chuck according to claim 1, wherein said ~~planner~~ planar electrode ~~comprises~~ includes a first electrode and a second electrode,

said first electrode ~~comprising:~~ including,

a disc portion arranged in the center of said ceramic layer~~;~~, and

a first extending portion extending from a part of the disc portion toward the outer peripheral edge of said ceramic layer~~;~~,

said second electrode ~~comprising:~~ including,

a second extending portion arranged opposite to said first extending portion ~~over~~ relative to said disc portion of said first electrode ~~and arranged in lacking portions of the plurality of said first C-shaped ring portions of said first electrode;~~, and

a circular ring portion connected to an outer edge of said second extending portion so as to form the ~~outermost~~ outer peripheral edge ~~portion~~ of said second electrode.

5. (Currently Amended) An electrostatic chuck according to claim 4, wherein said first electrode further ~~comprises~~ includes a plurality of first C-shaped ring portions at predetermined intervals so as to have different diameters, the first C-shaped ring portions extending in C shapes ~~in~~ from both sides of said first extending portion ~~surrounding~~ around said disc portion.

6. (Currently Amended) An electrostatic chuck according to claim ~~4~~ 5, wherein said second electrode further ~~comprises~~ includes a plurality of second C-shaped ring portions at predetermined intervals so as to have different diameters, the second C-shaped ring portions extending in C shapes ~~in~~ from both sides of said second extending portion and being engaged with ~~the~~ said plurality of ~~said~~ first C-shaped ring portions of said first electrode.

7. (Currently Amended) A method for manufacturing an electrostatic chuck, comprising ~~the steps of~~:

preparing a first disc-shaped ceramic material compact having a half of a thickness of a completed ceramic layer;

forming an electrode on a surface of said first ceramic material compact;

preparing a second disc-shaped ceramic material compact having a half of a thickness of the completed ceramic layer and having a cooling gas channel on its surface ~~within~~ in a location overlying said electrode;

placing said second ceramic material compact on said first ceramic material compact so as to form a laminate ~~and;~~

firing the entire laminate to form the completed ~~complete a~~ ceramic layer; and

bonding the completed ceramic layer to a metal base plate by means of an adhesive layer.

8. (Currently Amended) The method ~~Method~~ of claim 6, wherein said adhesive layer is flexible.